

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
	:	Examiner: Dahimene, Mahmoud
MASAHIKO KUBOTA ET AL.)	
	:	Group Art Unit: 1792
Application No.: 10/565,658)	
	:	Confirmation No.: 5506
Filed: January 24, 2006)	
	:	
For: LIQUID DISCHARGE HEAD)	
MANUFACTURING METHOD, AND	:	
LIQUID DISCHARGE HEAD)	
OBTAINED USING THIS METHOD	:	August 5, 2009

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

STATEMENT OF SUBSTANCE OF INTERVIEW

Sir:

Applicants' undersigned representative wishes to thank the Examiner and his Primary Examiner for the courtesies extended during the telephone interview of August 4, 2009. During the interview, Applicants' undersigned representative discussed the advantages of the claimed invention and how the claimed invention differed from the prior art. In particular, it was stressed that the features of the material used for the coating resin layer and at least a portion of the material of the solid layer have distinct advantages in minimizing scum in the liquid discharge head manufacturing method. Support for the claimed features in the specification were also discussed. Applicants also emphasized the differences between the applied art and independent

Claim 1. The Examiner agreed that at least the feature of the material used for the coating resin layer containing a cationically polymerizable resin and a basic material having a pair of nonshared electrons did not appear to be taught by the applied art. The Examiner advised that he would need to update his search before making a final determination on patentability.

Favorable consideration is requested.

Applicants' undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,

/Mark A. Williamson/

Mark A. Williamson
Attorney for Applicant
Registration No. 33,628

FITZPATRICK, CELLA, HARPER & SCINTO
30 Rockefeller Plaza
New York, New York 10112-3801
Facsimile: (212) 218-2200
MAW:ylr